



MICRO ENCODER INC.  
RELENTLESS INNOVATION

## An EKV Model User's Perspective: For Low-Power Circuits and Beyond

EKV Users' Meeting/Workshop,  
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Patrick Mawet, Principal Engineer  
Micro Encoder Inc

# Agenda

- MEI introduction
- Why use the EKV model?
- Our experience using the model in a low-power circuit
- Where to get the models?
- Beyond low-power circuits: using EKV model for analog IC design in general
- Concluding comments

# MICRO ENCODER INC.



- Founded 1986
- Subsidiary of Mitutoyo Japan
- Independent Washington State Corporation
- Located in Kirkland, WA, USA
- 63 employees
- Research and development of technologies for dimensional metrology and other applications
  - Initial focus was capacitive encoder technology (Digimatic)
  - QuickVision vision measurement software & research started 1994
  - Now continuing QV work and other advanced sensor research

# MEI's Work...

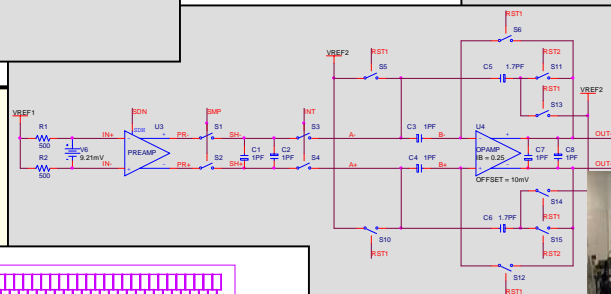
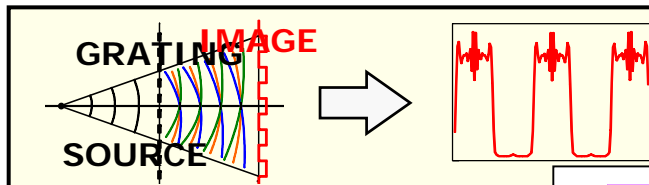
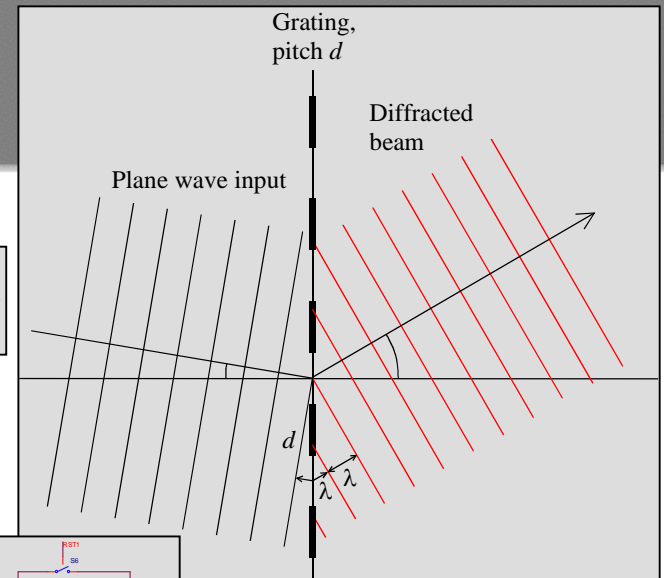
$$SIN'_i = \frac{2}{M} \sum_{m=0}^{M-1} S_i(\varphi_m - \delta) \sin(\varphi_m - i\alpha)$$

$$= \frac{2}{M} \sum_{m=0}^{M-1} [(1 + dr_i) \cos(\varphi_m - i\alpha) + \delta \sin(\varphi_m - i\alpha) + \varepsilon_i \sin(\varphi_m - i\alpha) + \mu_i] \sin(\varphi_m - i\alpha)$$

$$= \frac{1}{M} \sum_{m=0}^{M-1} [(1 + dr_i) \sin(2\varphi_m - i2\alpha) + \delta [1 - \cos(2\varphi_m - i2\alpha)] + \varepsilon_i [1 - \cos(2\varphi_m - i2\alpha)] + 2\mu_i \sin(\varphi_m - i\alpha)]$$

$$= \varepsilon_i + \frac{1}{M} \sum_{m=0}^{M-1} \delta - \frac{1}{M} \sum_{m=0}^{M-1} \delta \cos(2\varphi_m - i2\alpha)$$

$$c_n = \frac{1}{d} \int_{-l/2}^{l/2} T(x) e^{-i2\pi n \frac{x}{d}} dx = \frac{l}{d} \frac{\sin(\pi nl/d)}{\pi nl/d}$$



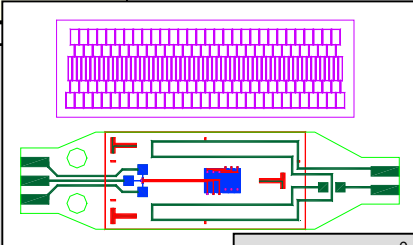
```

#ifndef QVAPI
if ( m_pPickListManager )
{
    QVRegistry& rRegistry = Singleton<QVRegistry>::Instance();
    int maxItems = m_pPickListManager->GetItemCount();
    for ( int i = 1; i <= maxItems; i++ )
    {
        PICK_LIST_ITEM item;
        m_pPickListManager->GetNthItem( i, &item, FALSE ); // i IS ONE-BASED

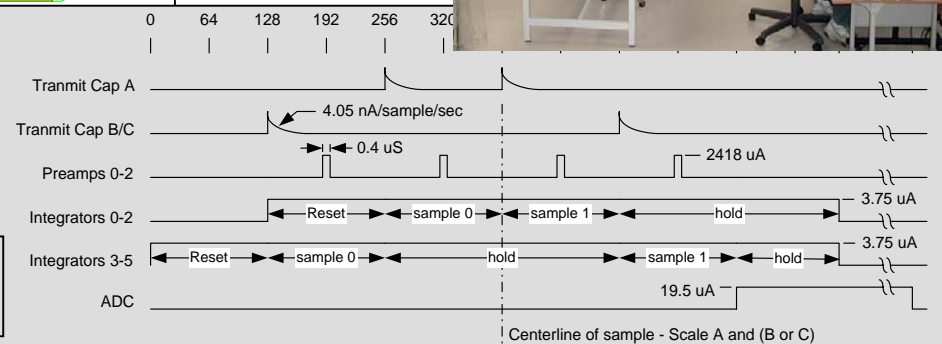
        CString czSubKey = VPSECTION_PROGRAMCONTROL;
        czSubKey += _T("\\PickList");
        TCHAR Str[5] = _T("**");
        _itot(i, Str, 10);
        czSubKey += Str;

        rRegistry.WriteString( czSubKey, _T("FileName"), item.m_szPath);
        rRegistry.WriteINT( czSubKey, _T("Start"), item.dwStart);
        rRegistry.WriteINT( czSubKey, _T("End"), item.dwEnd);
    }
    delete m_pPickListManager;
    m_pPickListManager = NULL;
}
#endif

```



$$U(x, z) = \frac{e^{i2\pi/\lambda - i\pi/4}}{\sqrt{2nn'}} \sum_{p=1}^{m'} T(x + pd/n) e^{ip^2/(2nn')} (1 + i^{nn'} (-1)^p)$$

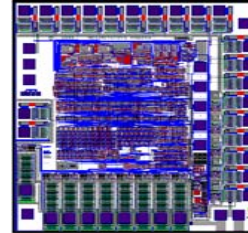


# Mitutoyo Products with MEI Technology

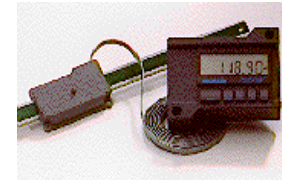
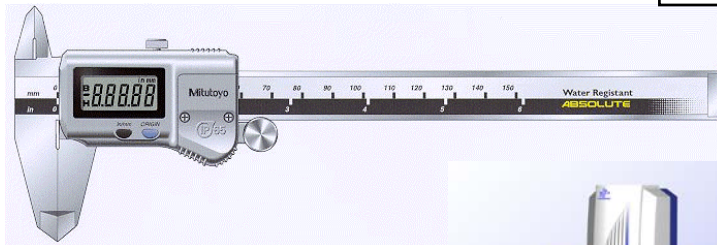
**DIGIMATIC**



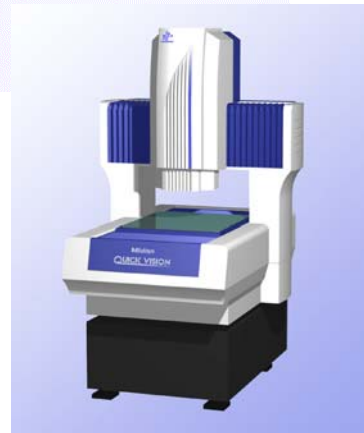
**Coolant Proof**



Coming soon



**QUICK VISION®**



**QVPAK®**



Coming soon

[www.mitutoyo.com](http://www.mitutoyo.com)

# Why use the EKV model...

...when there is a perfectly good 'industry standard' model supported by all the foundries and EDA tool vendors?

## Low power circuits:

- Better modeling of the weak and moderate inversion areas
- Initial intent of the model
- Most 'accepted' reason for using the model

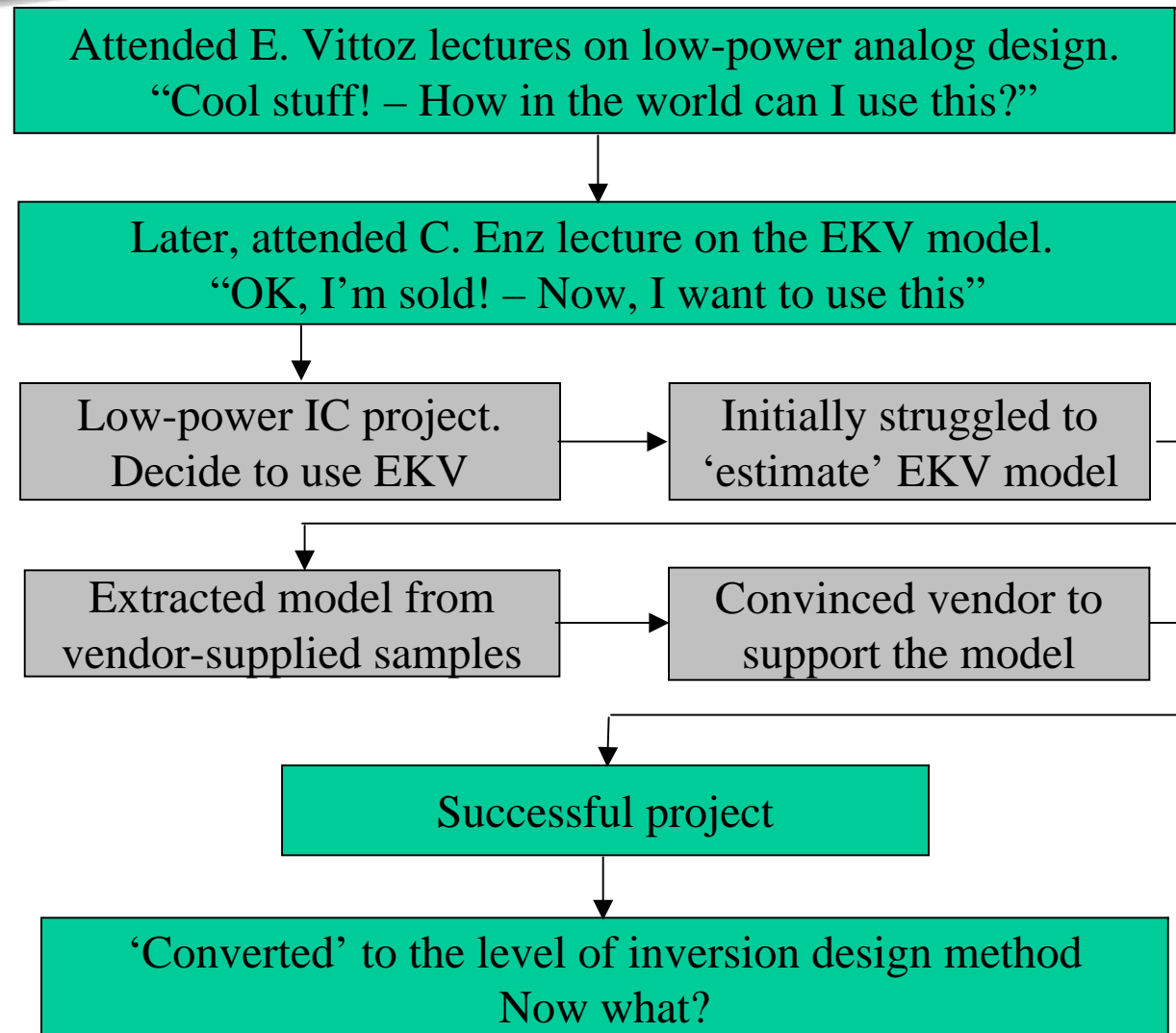
## Compact model:

- True 'compact' model (number of parameters)
- Hierarchical model: can be used both for simulations and hand calculation
- Faster simulations

## Analog IC design:

- Better modeling of  $g_m$  and noise, not just ID
- Analog circuits are usually biased with currents
- 'Level of inversion' design method

# My experience with the EKV model



# Getting started with the EKV model: a low-power (uAmps) analog circuit

- Many circuits used transistors in weak and moderate inversion
  - need for an accurate model through all modes of operations.
- At first, the foundry supplied us with transistor arrays to extract the model
  - We rented a HP4155B, and proceeded with doing our own extraction
  - We got reasonably good results, but not without challenges
- I presented the EKV model and its advantages for low-power design to the vendor.
- Eventually, the foundry's modeling expert 'bought' and studied the model, and the foundry supplied the models for this project (they have better hardware and software tools to do this).
- This was a successful story about promoting the model acceptance.

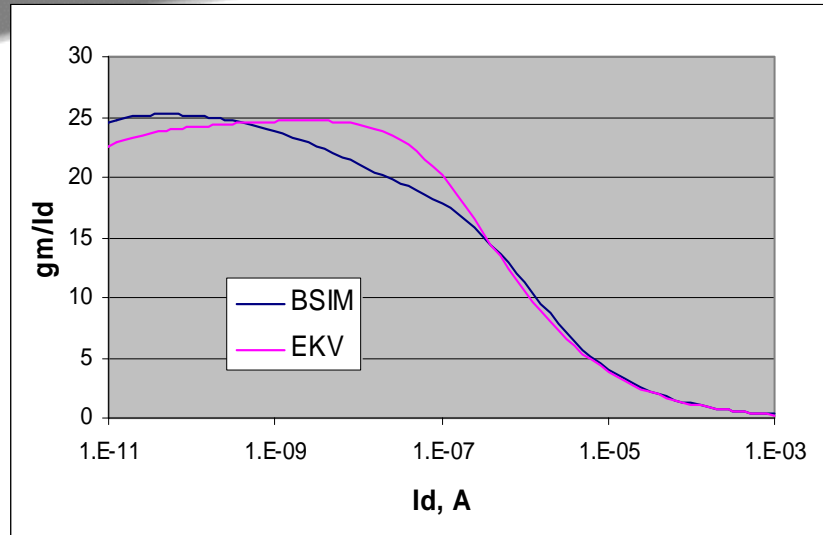


# EKV 2.6 extraction challenges

- I am a circuit designer, not a modeling expert! (However, MOS modeling is definitely an interest of mine).
- The model is simple (few parameters), but getting the best possible fit for all sizes/conditions is not so easy.
- Limitation in hardware/software.
  - Hardware: very low current measurements required – HP4155B worked well.
  - Software: used Pspice + Matlab + Excel – no real extraction system.
- Some of the specific difficulties I encountered:
  - Short-channel NMOS: difficulty in matching the drain current both at low and high gate voltages. (due to absence of 2<sup>nd</sup> order mobility reduction in EKV 2.6).
  - PMOS: difficulties in matching the drain current in both in linear and saturation regions.
- Solution: optimize the model for the project conditions.

# Where to get the models?:

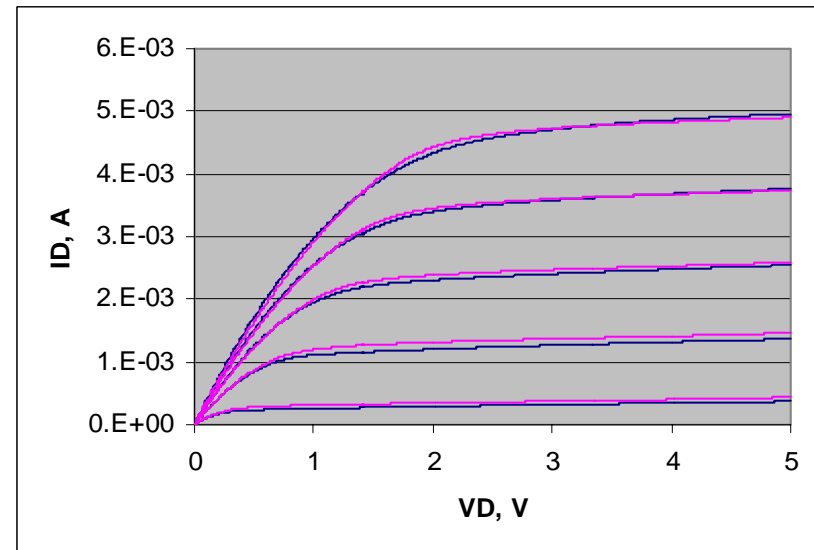
## 1. - 'Extract' from the BSIM model ('OK')



### Possible compromise:

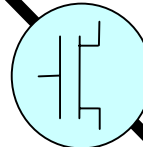
- Get typical transistors curves from the foundry (if willing).
- Replay the model against the curves for fine tuning.
- Good solution for a better model with minimal involvement from the foundry.
- 'Reality check'

- Often, it is the only available option.
- However, we are extracting from a model that is not 'perfect'.
- Upcoming tools?



# Where to get the models?:

## 2. - Extract from transistor samples (better)

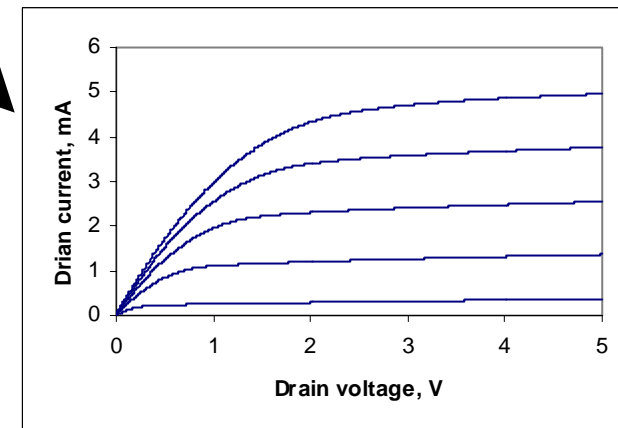


### Big questions/concerns:

- Typically, will work from a limited set of samples provided by the vendor.
- Are the samples representative of the 'typical' process?
- Requires some hardware (low current measurements).
- 'Good' extraction is not so easy.

### Use a qualified extraction service

- Better solution, but...
- May be expensive.
- The concerns about the transistor samples remain valid.



## Where to get the models?:

### 3. – Have the foundry supply the model (best)

- Best solution - the foundry has access to:
  - Knowledge of the process.
  - A lot of process data.
  - Extraction hardware/software.
- But... a lot of resistance
  - Difficult to convince the foundry to have to support another model.
  - Not 'industry standard'.
  - Traditionally, the market has been dominated by digital IC's.
  - However... mixed-signal SOC's are becoming more relevant! – SOC is the new 'buzz word'.
- Analog/mixed-signal foundries.
  - Should consider supporting the model for analog designers.
  - Low-power processes are prime candidates.

# Beyond low-power circuits: Analog circuit design

- The EKV model is also very good for analog circuits in general
  - Several features useful for the analog IC designer: matching parameters, estimation of drain/source parasitics...
  - The model can be easily used for hand calculations and optimization (see next slide).
  - The  $g_m/I_D$  equation is based on currents – most analog circuits are biased with currents – So, why base our calculations on a voltage ( $V_{dsat}$ )?
  - The model was designed by analog IC designers for analog IC designers.
  - The model is valid for all modes of operation (weak – moderate – strong inversion).
- The main roadblocks are model acceptance and availability. The 'industry standard' BSIM model dominates the industry.
- Need to educate designers, foundries and EDA vendors.

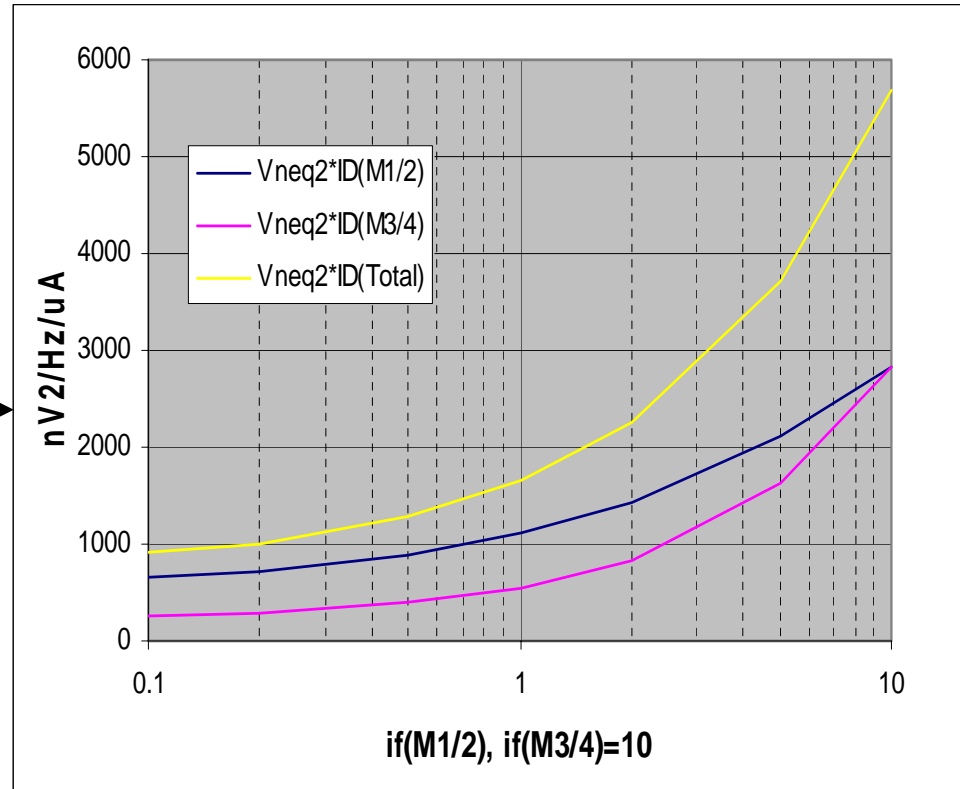
# Example of circuit optimization using the EKV - equations: low noise (not low power) op-amp:

$$i_f = \frac{I_D}{I_S}$$

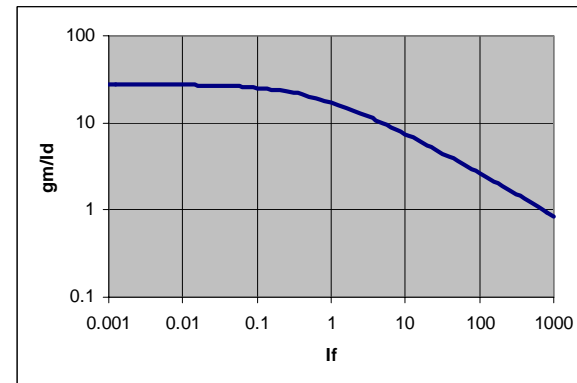
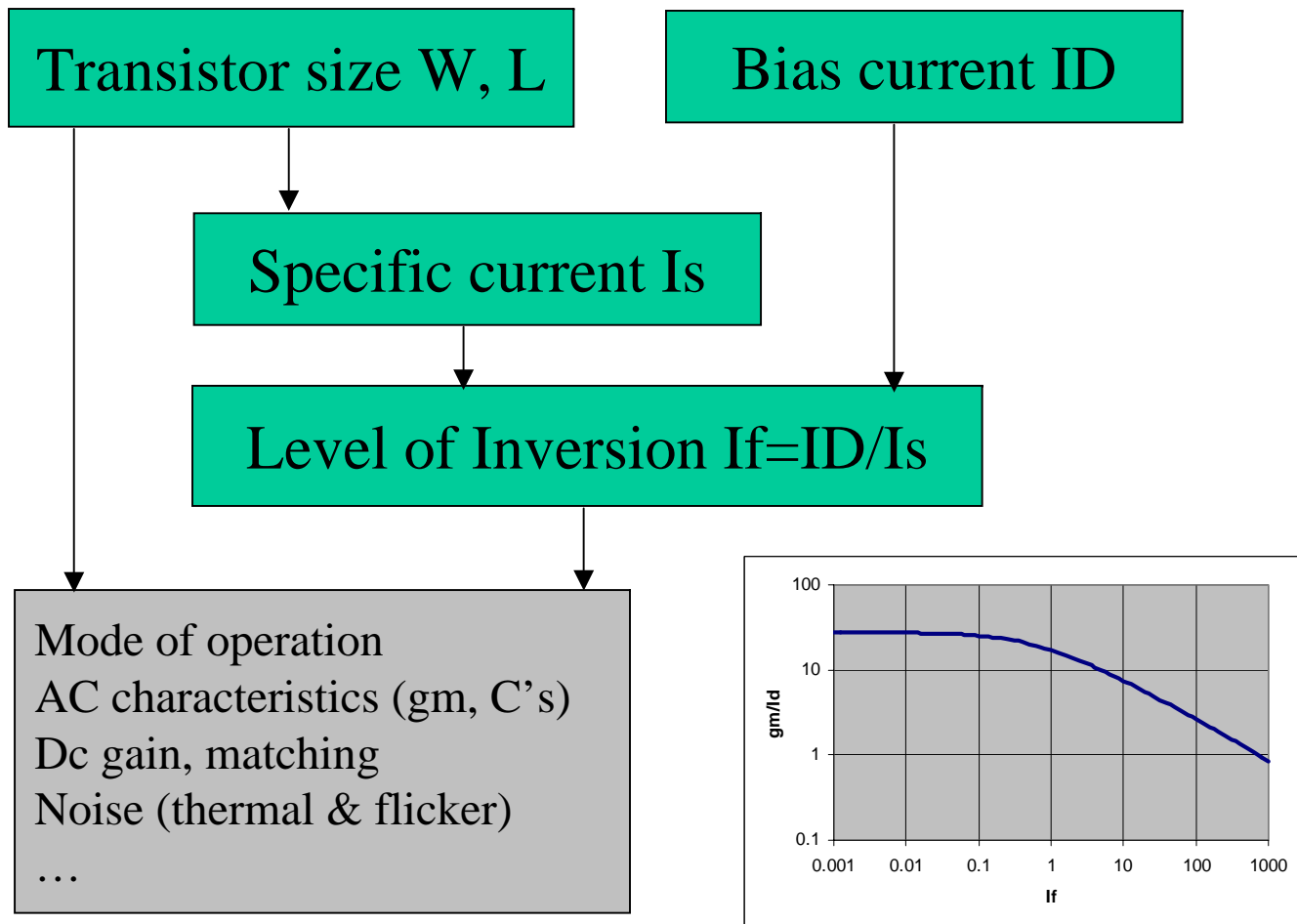
$$\frac{g_m}{I_D} = \frac{1}{n \cdot UT} \cdot \frac{2}{1 + \sqrt{4 \cdot i_f + 1}}$$

$$\gamma = n \cdot \frac{1}{1 + i_f} \cdot \left( \frac{1}{2} + \frac{2}{3} \cdot i_f \right)$$

$$V_n^2 = \gamma \cdot \frac{4KT}{g_m}$$



# EKV model -> Level of inversion design method for transistor sizing



# The Level of Inversion Methodology

- Uses continuous linear equations to calculate  $g_m$  and thermal noise from transistor size and bias current, valid for all modes of operation of the transistor.
- I used this method to optimize a low-noise amplifier, in a normal (not battery powered) application. This was very successful. However, the BSIM model was used for simulations. (In the moderate to strong inversion, the BSIM is OK, at least for  $g_m$ )
- More logical method of sizing transistors from the bias current.
- I now use this for all design. It just requires estimating the specific current for different transistor sizes (L).
- The level of inversion design method has now been presented in papers and seminars (D. Binkley, D. Foty) since then.



# Example of 'computer-aided hand calculations': My handy transistor calculator!

The screenshot shows a software window titled "Device Calculator" with four tabs: "Resistor", "Capacitor", "MOSFET", and "RC circuit". The "MOSFET" tab is active. It features two radio buttons for "NMOS" (selected) and "PMOS". Under "Electrical characteristics", there are input fields for  $W$ ,  $L$ , and  $M$  (all in green), and output fields for  $I_s$ ,  $I_d$ ,  $I_d/I_s$ ,  $g_m$ ,  $g_m/I_d$ ,  $C_l$ ,  $F$ ,  $C_g$ , and  $C_d$  (all in yellow). A "Size (outline)" section has input fields for  $X$ ,  $Y$ , and  $A$  (all in yellow), and an output field for  $V_d$  (in green). An "Exit" button is at the bottom.

Parameter	Value	Unit
$W$	10	$\mu\text{m}$
$L$	2	$\mu\text{m}$
$M$	1	
$I_s$	1.297	$\mu\text{A}$
$I_d$	10	$\mu\text{A}$
$I_d/I_s$	7.71	
$g_m$	77.1	$\mu\text{A/V}$
$g_m/I_d$	7.7	
$C_l$	10	$\text{pF}$
$F$	1.227	$\text{MHz}$
$C_g$	0.055	$\text{pF}$
$C_d$	0.009	$\text{pF}$
$X$	5.0	$\mu\text{m}$
$Y$	11.2	$\mu\text{m}$
$A$	56	$\mu\text{m}^2$
$V_d$	2.5	$\text{V}$

# Concluding comments

- The EKV model (2.6) is now supported by most EDA tools/simulators.
- It is a superior model for low-power analog IC design.
- The main issue for the user is ‘where to get the models’ – 3 different solutions.
- It is also a better model for analog IC design in general (‘level of inversion’ method).
- Any questions?



Patrick Mawet  
PRINCIPAL ENGINEER

[patrickm@microen.com](mailto:patrickm@microen.com)

Ph: 425.821.3906 • Fx: 425.821.3228 • [www.microen.com](http://www.microen.com)

11533 NE 118th Street • Kirkland, WA 98034, USA

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